



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

The application of:

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Serial No.: 10/619,052

Filed: July 10, 2003

For: **METHOD AND STRUCTURE FOR A SELF-ALIGNED
SILICIDED WORD LINE AND POLYSILICON PLUG
DURING THE FORMATION OF A SEMICONDUCTOR
DEVICE**

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§ GAU: 1765
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§ Examiner: Lan Vinh
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§ Atty. Docket: 2003-0076.00/US
§
§ Confirmation No.: 6083
§
§

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Commissioner for Patents
P.O. Box 1450
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I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail, postage prepaid, in an envelope addressed to: Commissioner for Patents, PO Box 1450, Alexandria, VA 22313-1450, on the date below:

August 28, 2006
Date


Signature

COMMENTS ON STATEMENT OF REASONS FOR ALLOWANCE

Applicant submits that each one of the claims of the captioned application is allowable over the cited art for reason of the cited art failing to disclose or suggest the features and/or combination of features as are defined therein. Although applicant acknowledges the Examiner's reasons for allowance as set forth with the Office Action of July 8, 2006, Applicants submit that the reasons for allowance as provided by the Examiner may represent merely a portion of all of the reasons that support the patentability of the claims of the present application without necessarily being exhaustive.

If there are any matters which may be resolved or clarified through a telephone call, the Examiner is cordially invited to contact the undersigned.

Respectfully submitted,



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